Properties of polyamorphous Ce75Al25 metallic glasses

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The thermal stability and electronic transport properties of polyamorphous Ce₇₅Al₂₅ metallic glass (MG) have been investigated using *in situ* high-pressure, high-temperature, energy-dispersive synchrotron x-ray diffraction and in situ high-pressure and low-temperature, four-probe resistance measurements. The results are compared with the properties of La75Al25 MG. The pressure dependence of the crystallization temperature and resistance of the Ce₇₅Al₂₅ MG exhibited turning points at the polyamorphic transition pressure, 1.5 GPa, and they clearly presented different behaviors below and above 1.5 GPa. In contrast, no turning points were observed in the $La_{75}Al_{25}$ MG (La has no 4f electron). Additionally, the pressure-tuned temperature coefficient of resistance of the Ce75Al25 MG was observed. These results revealed switchable properties in the polyamorphous Ce75Al25 MG that are linked with 4f electron delocalization.

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Metallic glasses (MGs) with disordered structures exhibit many unique properties that put these materials at the forefront of materials research.^{1,2} Phase transitions in materials often cause a change in their properties, e.g., mechanical, thermal, electrical, magnetic, or optical properties, which could be employed to produce switchable engineered materials, e.g., shape memory alloys, phase-change rewriteable storage, thermal magnetic switchers, etc. Polyamorphism,^{3,4} in which multiple distinct amorphous phases (states) are formed from the same substance, has been extensively investigated in nonmetallic amorphous systems, e.g., amorphous ice,^{5,6} oxides,⁷⁻¹¹ chalcogenides,^{12,13} silicon,¹⁴ etc. These amorphous materials generally have directional and lowcoordination (<6) local environments. The polyamorphic transition from a low-density amorphous (LDA) state to a high-density amorphous (HDA) state under pressure often results from increased atomic coordination and was thought to be impossible in MGs, which most likely have densely packed atomic structures with the maximum coordination number (11–14) among random nearest neighbors.¹⁵

Surprisingly, pressure-induced polyamorphic transitions were recently discovered in Ce-bearing MGs.^{16–18} These results raise an interesting question: which of the unique properties of MGs can be tuned by the polyamorphic transition and how? Until now, only Liu et al.¹⁹ have reported electrical resistance and thermometric measurements on La68Al10Cu20Co2 and Nd60Al10Ni10Cu20 bulk MGs (BMGs) under high pressure, and the two materials presented sharp changes in resistance at about 1.4 GPa and 1.1 GPa, respectively. These changes in resistance were claimed to be due to polyamorphic transitions in $La_{68}Al_{10}Cu_{20}Co_2$ and Nd₆₀Al₁₀Ni₁₀Cu₂₀ BMGs, although no direct experimental evidence for pressure-induced polyamorphic transitions in either BMG was reported. According to results obtained from *ab initio* calculations and experiments,^{16-18,20,21} the unique polyamorphic transition in Ce-bearing MGs is due to 4f electron delocalization under pressure. Thus, it is puzzling to observe similar polyamorphism in the La₆₈Al₁₀Cu₂₀Co₂ MG, which has no 4f electrons. Furthermore, x-ray diffraction (XRD) results, taken at pressures up to 40 GPa, suggested no transition for La₇₅Al₂₅ MG under high pressure.²² Very recently, Zeng et al.¹⁸ experimentally confirmed an electronic polyamorphic transition at 1.5 GPa in the Ce75Al25 MG. Thus, it is very desirable to examine the differences in the properties of the LDA and HDA MGs. In this work, we investigated the crystallization behavior and resistance of the Ce₇₅Al₂₅ MG, as a prototype system, along with the La₇₅Al₂₅ MG for comparison, using in situ high-pressure, hightemperature energy-dispersive x-ray diffraction (HPHT-EDXRD) and in situ high-pressure, low-temperature fourprobe resistance measurements to address whether properties change at the polyamorphic transition in the polyamorphous Ce75Al25 MG. Different thermodynamic and electrical transport properties are clearly revealed in the LDA and HDA Ce₇₅Al₂₅ MG, linked to 4f electron delocalization in Cebearing MGs. These findings might promote potential applications that utilize the LDA and HDA MGs.

Ce₇₅Al₂₅ and La₇₅Al₂₅ MG ribbons with a thickness of

about 25 μ m and a width of about 1.5 mm were prepared through single-roller melt spinning. Master ingots were prepared by arc-melting a mixture of pure cerium (99.5at. %), lanthanum (99.5at. %), and aluminum (99.95at. %) in a zirconium-gettered argon atmosphere. They were remelted five times to ensure homogeneity in the composition. The pressure dependences of the crystallization onset temperatures (T_x) of the Ce₇₅Al₂₅ and La₇₅Al₂₅ MG were measured from about 0.1 to 4.2 GPa by in situ HPHT-EDXRD. The measurements were performed with a multianvil pressure apparatus in a 250-ton hydraulic press and synchrotron radiation x rays from the MAX80 beamline at HASYLAB in Hamburg, Germany.²³ Hexagonal boron nitride (BN) powder was used as the pressure medium. The diffraction angle θ was set at 4.514°. The temperature was measured by a thermocouple with a stability of ± 1 K. Each run consisted of an isothermal room-temperature compression stage followed by isobaric heating to high temperature at a rate of 15 K/min. The pressure of the sample was calculated from the lattice constant of NaCl using the Decker equation of state.²⁴ The HPHT-EDXRD patterns were recorded every 20 s to monitor the crystallization at different pressures. The uncertainty in the estimated T_x under pressure was about 5 K. The T_x values of the Ce₇₅Al₂₅ and La₇₅Al₂₅ MGs were measured at ambient pressure by a differential scanning calorimeter (DSC) (Perkin-Elmer DSC-7) with a heating rate of 20 K/min in Ar flow. The in situ high-pressure, low-temperature four-probe resistance measurements were performed with both a manual circuit^{25,26} four-probe-electrode and an integrated microcircuit²⁷ in a Mao-type diamond anvil cell (DAC) and a L-He cryostat. In the manual four-probe-electrode circuit method, the T301 gasket that lies between the diamond anvils was preindented to 20 GPa and its thinnest part was removed. Then, a cubic BN/epoxy mixture powder was added inside the indent, which was then pressed to 20 GPa again, reliably insulating the sample and electrodes against the T301 gasket and serving as a quasihydrostatic pressure medium for the sample. Four electrodes were made of platinum foil with a thickness of 4 μ m. The samples were cut into $380 \times 100 \times 25 \ \mu m^3$ chips, placed on top of the anvil, and pressed into the BN/epoxy layer together with the electrodes. The variation in pressure across the sample was less than 1 GPa in the studied pressure range. A ruby scale was used to determine the pressure through the optical window of the cryostat during the entire cooling process. In our experiments, pressure was generated by a pair of diamonds with 400 μ m diameter tips. The electrodes and the gaskets were observed with a microscope in reflection light, and no contact between them was found at any stage in the experiments.

Crystallization often occurs via nucleation and growth processes when heating MGs and can greatly modify their properties. Thus, the crystallization behaviors of MGs are important in both their synthesis²⁸ and their applications.²⁹ Utilizing the HPHT-EDXRD technique, we studied the crystallization behaviors of the Ce₇₅Al₂₅ MG from about 0.1 to 4.2 GPa, which covers the pressure range in which the LDA to HDA Ce₇₅Al₂₅ MG polyamorphic transition occurs. Figures 1(a) and 1(b) show HPHT-EDXRD patterns of Ce₇₅Al₂₅ MG at 1.1 GPa and 3.0 GPa, respectively. Before crystallization, broad amorphous peaks are located at about 29.4 keV



FIG. 1. (Color online) *In situ* HPHT-EDXRD patterns from $Ce_{75}Al_{25}$ MG, recorded at various temperatures under (a) 1.1 GPa and (b) 3.0 GPa and from $La_{75}Al_{25}$ MG under (c) 0.3 GPa. The crystallization phases for each sample are identical over the entire pressure range studied, and their diffraction peaks are marked by hcp Ce_3Al in (a) and (b) and cubic La_3Al in (c). Some other diffraction peaks for boron nitride, originating from the sample holder, are marked by BN, and four fluorescence peaks from Ce or La also are marked.

and about 30.3 keV under 1.1 GPa and 3.0 GPa, respectively, together with two Bragg peaks from the hexagonal BN and four fluorescence peaks from Ce. Two sharp Bragg peaks emerged over the broad amorphous peak, indicating the onset of crystallization at 423 K in Fig. 1(a) and at 438 K in Fig. 1(b), these temperatures are the estimated values of T_x . The Ce₇₅Al₂₅ MG crystallized into the same hcp Ce₃Al phase (space group $P6_3/mmc$), which is the stable phase for Ce₃Al at ambient pressure, in the entire studied pressure range of 0.1–4.2 GPa.³⁰ To clarify the effect of the 4*f* electrons,



FIG. 2. (Color online) Crystallization onset temperatures T_x of Ce₇₅Al₂₅ and La₇₅Al₂₅ MGs as functions of pressure. The data at ambient pressure were estimated from the DSC measurements and are marked by red solid stars.

HPHT-EDXRD measurements were also performed on the La₇₅Al₂₅ MG. Figure 1(c) illustrates HPHT-EDXRD patterns of the La₇₅Al₂₅ MG at 0.3 GPa. The La₇₅Al₂₅ MG crystallized into its stable cubic La₃Al phase (space group Pm3m) over the entire pressure range of 0.1-4.2 GPa. Figure 2 shows T_x as a function of pressure for the Ce₇₅Al₂₅ and $La_{75}Al_{25}$ MG. The applied pressure affects the T_r of both samples and the two samples exhibit different behaviors. The T_x of the Ce₇₅Al₂₅ MG initially decreases with increasing pressure, until 1.5 GPa, and then increases with increasing pressure, up to 4.2 GPa. This turning point at 1.5 GPa coincides with the reported LDA-to-HDA polyamorphic transition pressure of Ce₇₅Al₂₅ MG,¹⁸ which indicates the different thermodynamic properties (different crystallization mechanism) of the LDA and HDA $Ce_{75}Al_{25}$ MG. In contrast, the T_x of the La₇₅Al₂₅ MG exhibits a monotonic linear increase with increasing pressure, with a positive slope of about 3.7 K/GPa from 0.1 to 4.1 GPa. This result suggests that no LDA-to-HDA polyamorphic transition occurred in the La₇₅Al₂₅ MG, which is consistent with the smoothly decreasing volume of La₇₅Al₂₅ MG under high pressure.²²

The crystallization of MGs under high pressure is generally controlled by competition between the thermodynamic potential barrier of nucleation ΔG^* and the atomic diffusion activation energy Q_n , which includes the effects of pressure on the molar volume change, molar free energy change, the elastic energy induced by volume change, interfacial energy between the amorphous phase and its crystalline counterpart, and atomic mobility.³¹ In general, pressure could decrease T_x by reducing ΔG^* between the MG and its crystalline counterpart and increase T_x by depressing the atomic mobility (increasing Q_n).³¹ The negative dT_x/dP observed below 1.5 GPa in the Ce75Al25 MG sample could be controlled by a decreasing ΔG^* in the LDA Ce₇₅Al₂₅ MG phase, which is in contrast to the positive slope of the La₇₅Al₂₅ MG sample over this pressure range. However, above about 1.5 GPa, the T_x of both the Ce₇₅Al₂₅ and the La₇₅Al₂₅ MG samples increase with pressure. T_x has a slope of about 33 K/GPa in the $Ce_{75}Al_{25}$ MG (1.5–4.2 GPa), higher than the typical 0–30 K/GPa in other MGs in the pressure range of 0-4 GPa.^{23,31,32}



FIG. 3. (Color online) (a) Resistances of $Ce_{75}Al_{25}$ and $La_{75}Al_{25}$ MGs as functions of pressure at ambient temperature. (b) The temperature dependences of the resistance of $Ce_{75}Al_{25}$ MG at ambient pressure, 1.5 and 12 GPa.

Because the onset of the LDA-to-HDA transition in Ce₇₅Al₂₅ MG at 1.5 GPa is accompanied by 4*f* electron delocalization, which makes the electronic structure of Ce become similar to that of La, thus, it is reasonable that dT_x/dP is positive above 1.5 GPa for HDA Ce₇₅Al₂₅ MG. Furthermore, 4*f* electron delocalization causes a volume collapse (densification) in HDA Ce₇₅Al₂₅ MG (1.5–4.2 GPa). This densification effect of pressure is seldom in the MG systems studied before, which could cause a decrease in atomic mobility, i.e., an enhancement of activation energy Q_n , and consequently result in a large dT_x/dP of 33 K/GPa observed in the HDA Ce₇₅Al₂₅ MG.

Electronic transport properties were investigated through the relative resistance of the LDA and HDA Ce₇₅Al₂₅ MGs, shown in Fig. 3 together with La₇₅Al₂₅ MG for comparison. The resistance of the Ce₇₅Al₂₅ MG at ambient temperature, shown in Fig. 3(a), decreases with increasing pressure and exhibits a transition starting at about 2 GPa and ending at about 6 GPa, connected to two distinct states, which resemble the LDA-HDA transition observed through XRD.¹⁸ The relatively wide transition range should be caused by the quasihydrostatic pressure conditions of this experiment. [Note that helium as a best hydrostatic pressure medium was used in the XRD experiments.¹⁸ The gaps in data points in Fig. 3(a) were just caused by the accidental jumps of pressure (less than 1 GPa) during the pressure increasing via DAC screw rotation by hand.] For comparison, it was found that the resistance of the La75Al25 MG does not exhibit an obvious transition as the Ce75Al25 MG does, although the resistance of the La75Al25 MG decreases with pressure. For their different curvatures of resistance vs pressure curves, we still do not know the exact origin, which might be caused by their different electronic structures (with and without 4f electron). According to Ziman-Faber theory, the resistance of a MG is primarily dominated by scattering from the intrinsically disordered atomic arrangements rather than thermal phonon scattering, which closely relates the resistivity to the scattering structure factor S(q).^{33,34} Electrical properties are supposed to be sensitive (more so than XRD) to such an electronic-structure-based polyamorphic transition. However, the quasihydrostatic pressure conditions in this resistance experiment may mess it. Additionally, the pressure effect on resistance is very complex in MG, and generally depends on many factors, e.g., the pressure dependence of Fermi wave vector k_F , Fermi energy E_F , volume V, and structure factor at $q=2k_F$, $S(2k_F)$ and single-ion pseudopotential of the constituent atoms. Approximately, it is related to the linear compressibility.^{35–37} The resistance of the $Ce_{75}Al_{25}$ MG at 14 GPa decreased by about 18% from its value at ambient pressure, which is roughly consistent with the linear compressibility at 14 GPa (11%) estimated by XRD.¹⁸ To further reveal differences in the electronic transport properties of the LDA and HDA Ce75Al25 MGs, the temperature coefficient of resistance (TCR) of the Ce75Al25 MG was measured at three pressures and is shown in Fig. 3(b). The pressure in the DAC was found to be unstable during cooling until the temperature was below 110 K, as the DAC shrinks during cooling. Thus, only the data below 110 K are shown in Fig. 3(b). At ambient pressure, the LDA Ce75Al25 MG exhibits a negative TCR equal to about -1×10^{-4} K⁻¹, which is consistent with the typical TCR value in MGs.^{38,39} According to Ziman-Faber theory, this negative TCR indicates that $2k_F \approx k_P$ in LDA Ce₇₅Al₂₅ MG, where k_p is the position of the first peak in the static structure factor.^{33,38} The sample exhibits a resistance minimum at about 8 K, and then the resistance increases rapidly with decreasing T, which is attributed to the Kondo interaction between the local 4f electrons and the conduction electrons in Ce-bearing materials.³⁹ However, at 1.5 GPa the 4f electrons in the $Ce_{75}Al_{25}$ MG start to delocalize, resulting in a positive TCR of about 5×10^{-4} K⁻¹ at 110 K. No Kondo effect feature is present; instead, a residual resistance plateau exists below 8 K. A similar disappearance of the Kondo feature at low temperature was reported in the crystalline intermetallic Ce₃Al compound under high pressure, which had been suggested to resemble the γ - α transition in Ce.⁴⁰ The HDA Ce₇₅Al₂₅ MG at 12 GPa, in which a large fraction of 4*f* electrons delocalize, has a positive TCR of about 9×10^{-4} K⁻¹, and the residual resistance plateau extends to about 20 K. The unique 4*f* electron delocalization during the LDA to HDA polyamorphic transition in Ce₇₅Al₂₅ at 1.5 GPa increases the number of conduction electrons, which may shift $2k_F$ away from k_P .³⁴ Consequently, the TCR can change from a negative value at ambient pressure to a positive value above 1.5 GPa. This kind of pressure-tuned TCR from a negative to a positive value in MGs under pressure is seldom observed before. These property changes are also reversible, as is the electronic polyamorphic transition in Ce-bearing MGs.^{16,20}

In conclusion, using in situ HPHT-EDXRD and in situ high-pressure, low-temperature, four-probe resistance measurements, we have observed changes in the thermodynamic and electronic transport properties accompanying the polyamorphic transition in the Ce75Al25 MG. This transition is linked to the unique 4f electron delocalization in Cebearing MGs. Below 1.5 GPa, for the LDA Ce₇₅Al₂₅ MG, dT_r/dP is negative and becomes positive above 1.5 GPa after the transition to the HDA Ce₇₅Al₂₅ MG, although the same crystalline phase was detected over the entire pressure range studied. In resistance measurements at ambient temperature, the HDA Ce₇₅Al₂₅ MG exhibits a lower resistance than the LDA Ce₇₅Al₂₅ MG. A pressure-tuned TCR, which shifted from negative to positive values, was observed during the polyamorphic transition in Ce75Al25 MG. These results have revealed that the LDA and HDA Ce75Al25 MG phases do have different properties, which will trigger further investigations into fabricating HDA MGs with interesting properties.

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